

Supplementary Materials

Manipulable Electronic and Optical Properties of Two-Dimensional MoSTe/MoGe₂N₄ van der Waals Heterostructures

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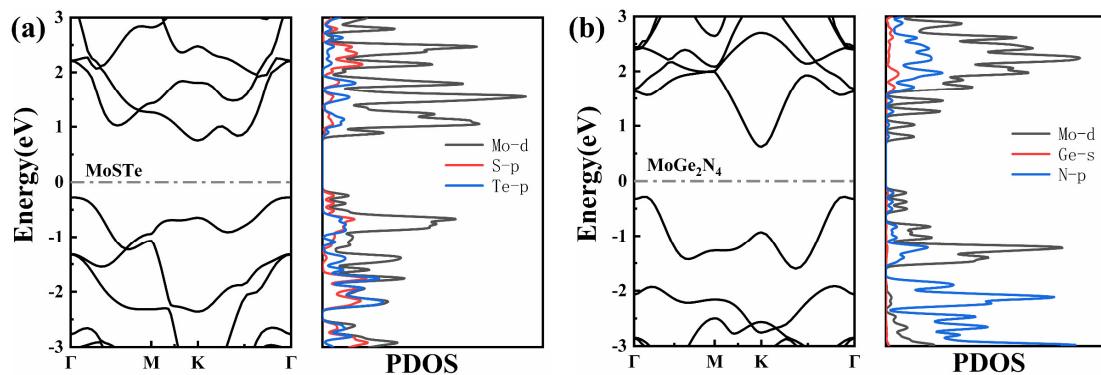


Figure S1. Band structures and PDOS of (a) Janus MoSTe monolayer and (b) MoGe₂N₄ monolayer, respectively. The Fermi levels are set to zero.

Table S1. : Binding energies (E_b) of the optimized MoSTe/MoGe₂N₄ vdWH for the twelve different stacking patterns.

Heterostructure	Te ₁	Te ₂	Te ₃	Te ₄	Te ₅	Te ₆
E_b (meV)	-6.7680	-6.7679	-6.7671	-6.7710	-6.7670	-6.7708
Heterostructure	S ₁	S ₂	S ₃	S ₄	S ₅	S ₆
E_b (meV)	-6.7396	-6.7407	-6.7405	-6.7434	-6.7427	-6.7394

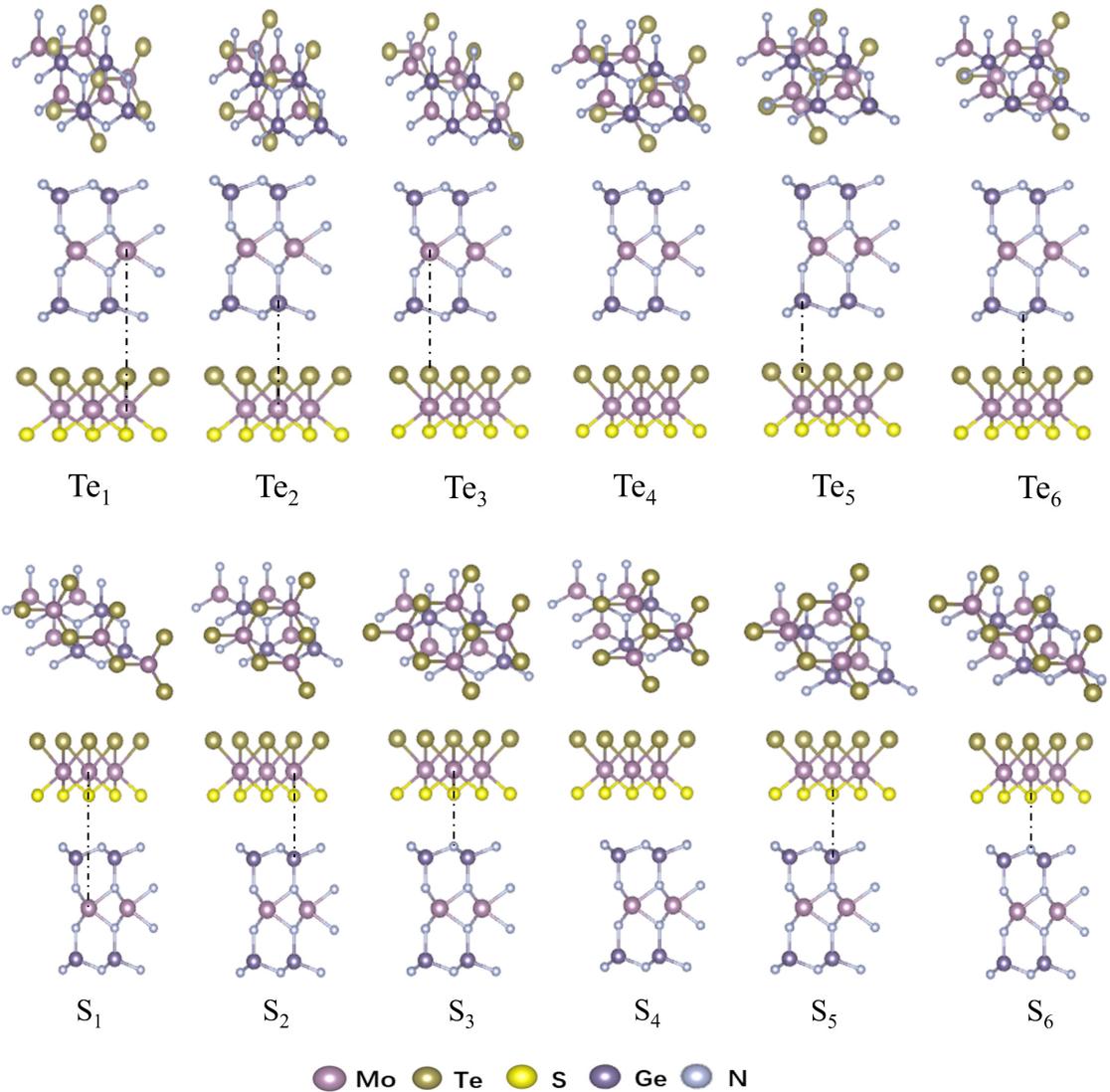
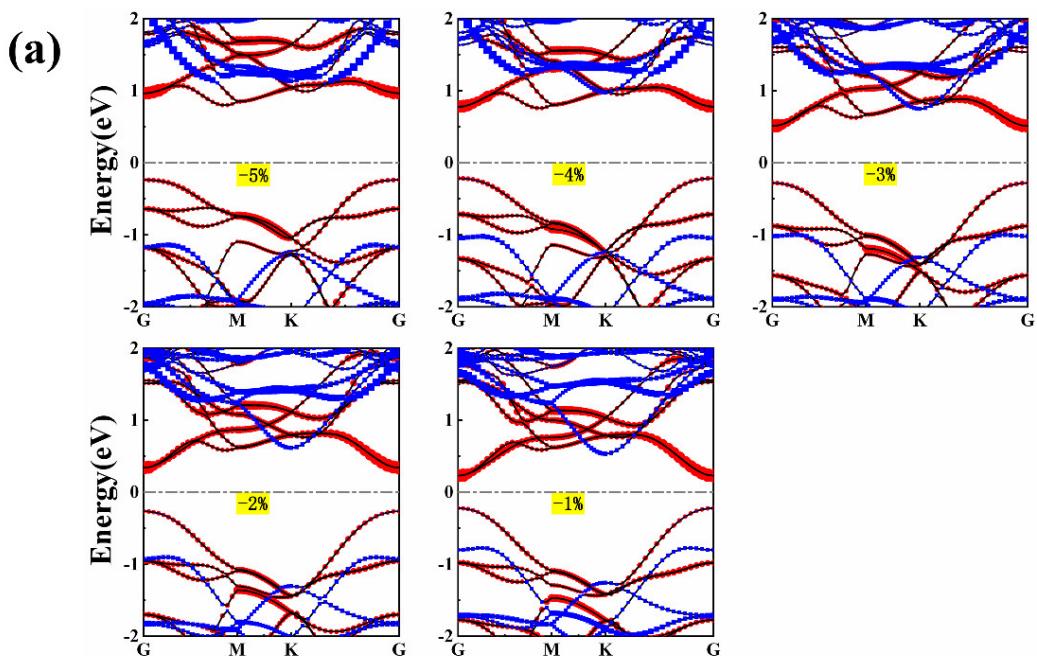
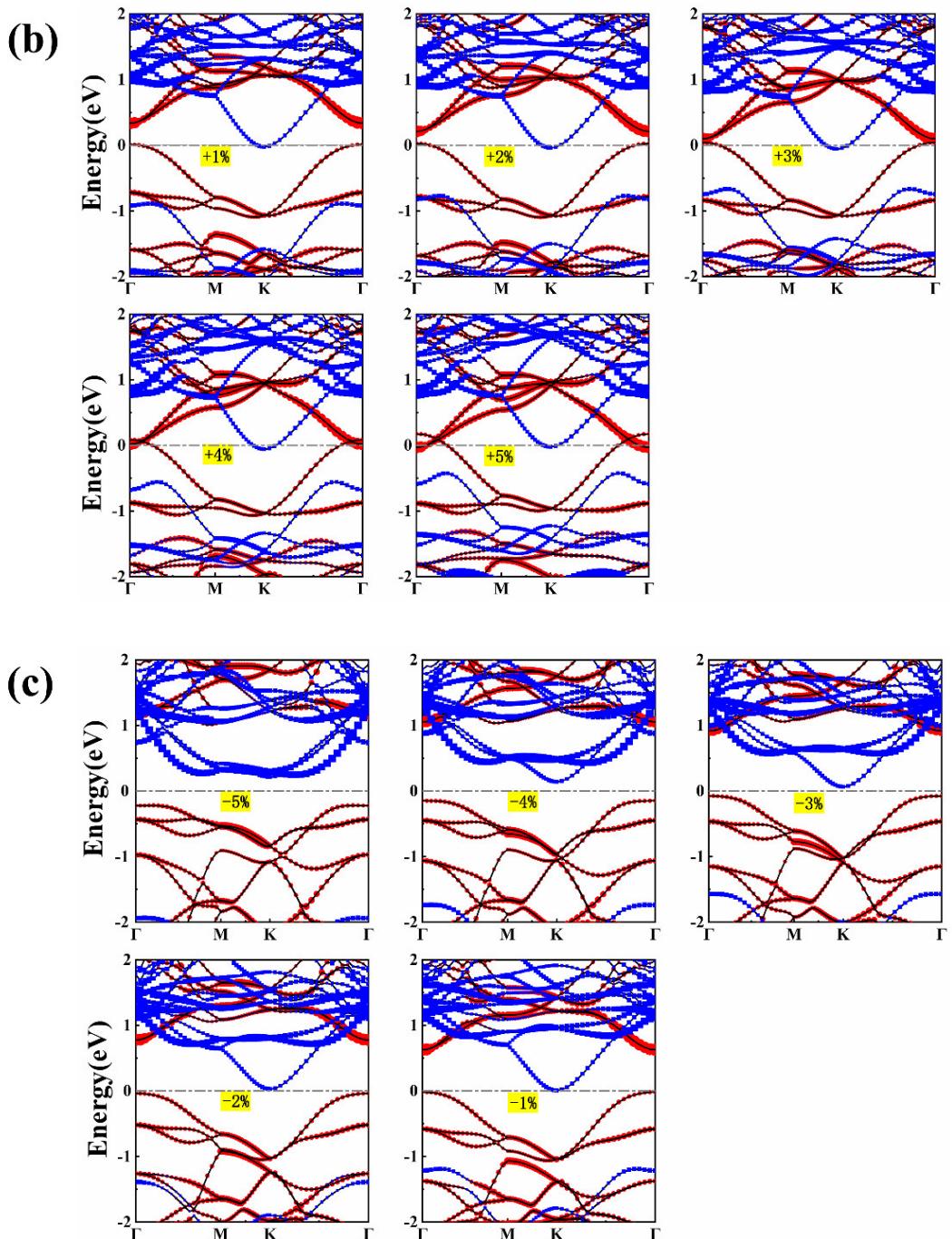


Figure S2. The optimized top and side views of the MoSTe/MoGe₂N₄ vdWH for twelve different stacking patterns.





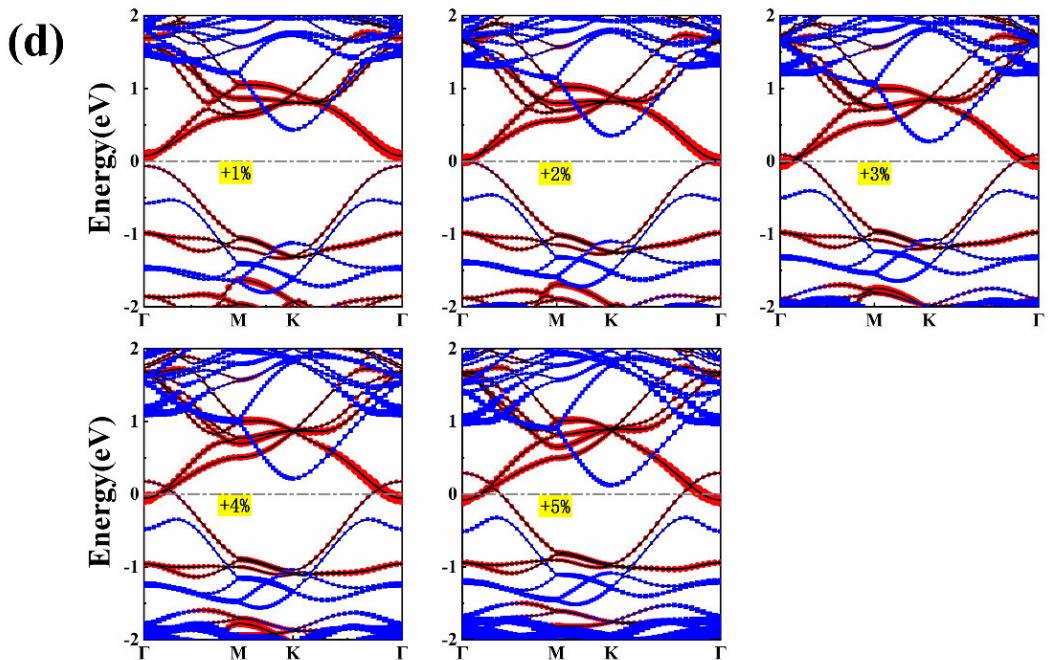
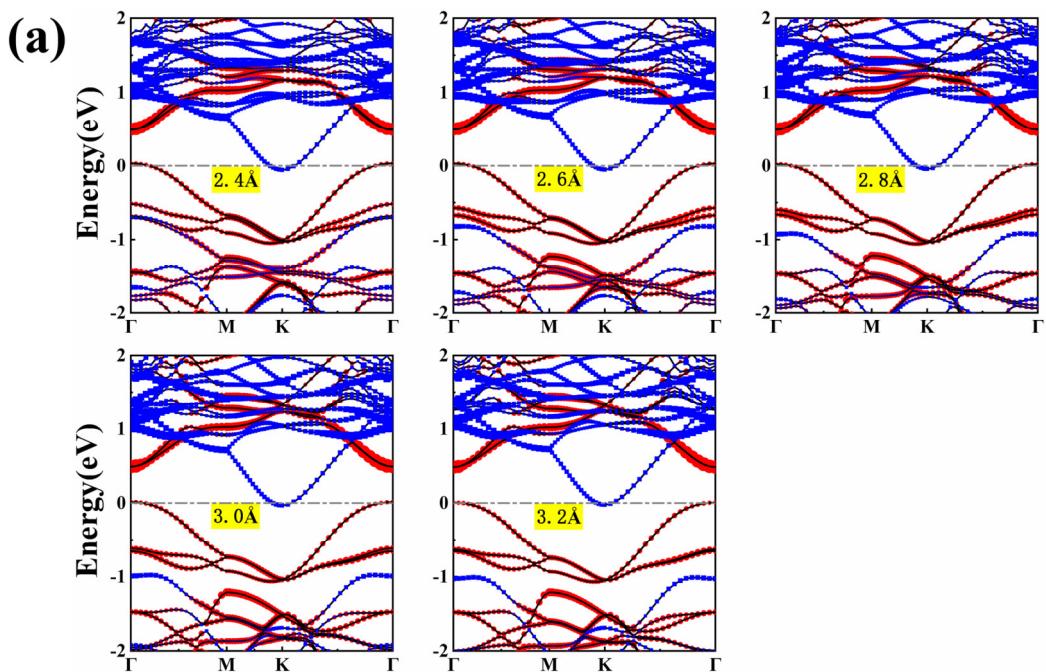
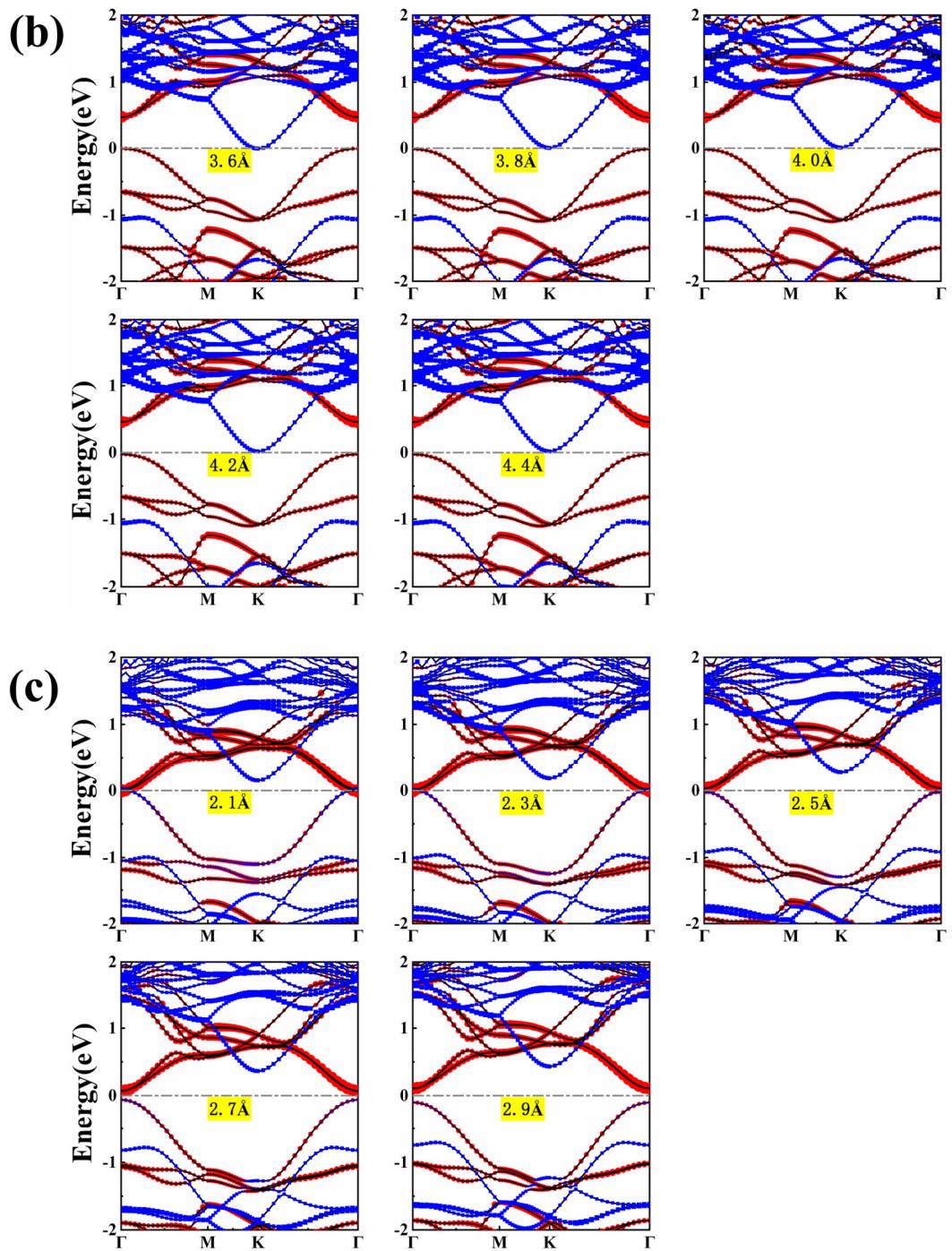


Figure S3. Band structures of (a) (b) Te₄-MoSTe/MoGe₂N₄ vdWH, (c) (d) S₄-MoSTe/MoGe₂N₄ vdWH under biaxial strains. The red and blue represent the weights from Janus MoSTe and MoGe₂N₄ monolayers, respectively. Negative and positive values mean compressive stress and tensile stress.





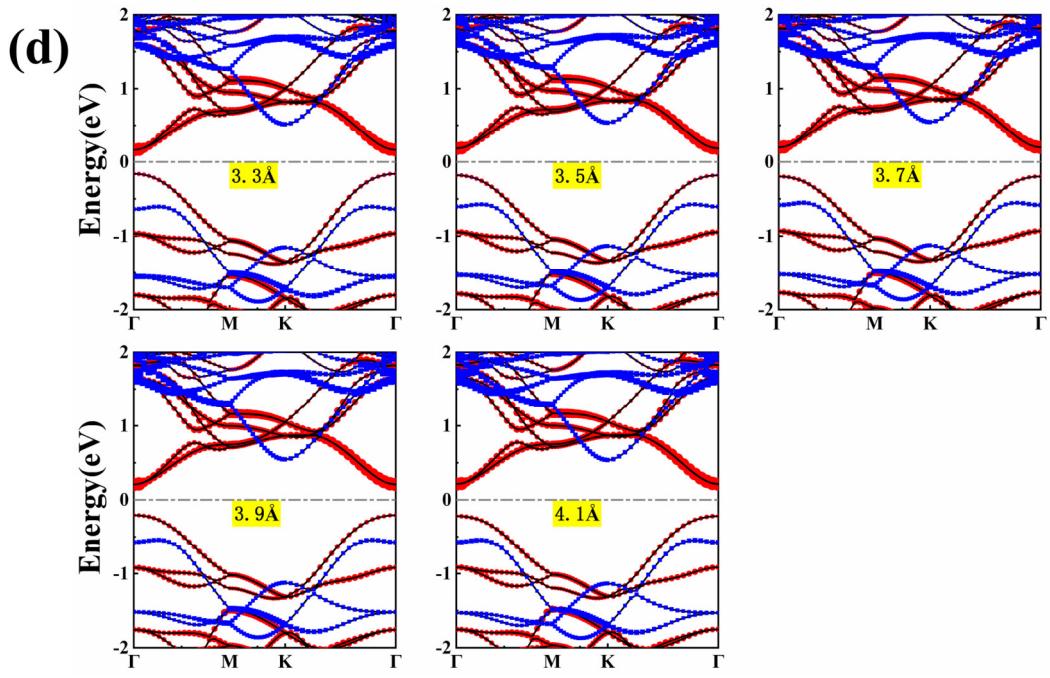


Figure S4. Band structures of (a) (b) Te₄-MoSTe/MoGe₂N₄ vdWH, (c) (d) S₄-MoSTe/MoGe₂N₄ vdWH under different interlayer distances, where the equilibrium interlayer distances are 3.4 Å and 3.1 Å, respectively. The red and blue represent the weights from Janus MoSTe and MoGe₂N₄ monolayers. .